

67,200-477
2000-0636

ABSTRACT

0045 A method for reducing light reflectance in photolithographic manufacturing process is disclosed including providing an inter-metal dielectric (IMD) layer including at least one via opening extending substantially perpendicular to a thickness therethrough, and, conformally forming an anti-reflectance coating (ARC) layer over said IMD layer such that the ARC layer is formed over sidewalls of the at least one via opening to reduce light reflectance.